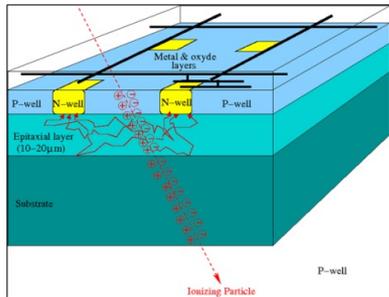
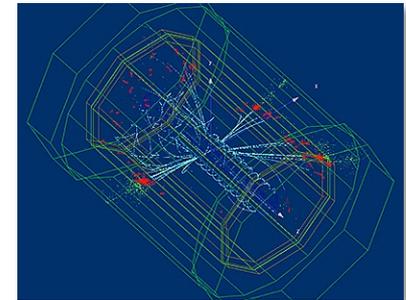


# CMOS Pixel Sensors for an FCC Vertex Detector



Ziad EL BITAR, Auguste BESSON

On behalf of the  
PICSEL group & C4PI Platform



PICSEL



C4PI-Platform



# Outline

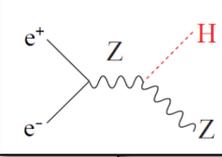
- Introduction: requirements & strategy
- MIMOSIS chip development (IPHC-IKF-GSI Collaboration)
- 65 nm R&D (with CERN EP R&D WP 1.2 & ALICE ITS-3)
- Stitching and bending
- Conclusion & Synergies in CMOS R&D

	Z	Higgs	ttbar
$\sqrt{s}$ [GeV]	91.2	240	365
Luminosity / IP ( $10^{34}\text{cm}^{-2}\text{s}^{-1}$ )	230	8.5	1.7
no. of bunches / beam	16640	393	48
Bunch separation (ns)	20	994	3000

# Higgs Factory Vertex detector requirements

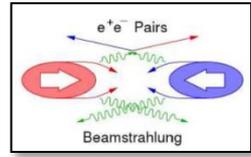
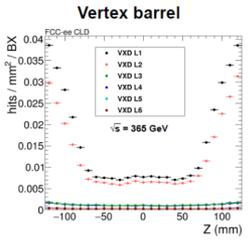
Physics

- ⇒ Flavour tagging
- ⇒ Low pT tracks
- ⇒ Vertex/Jet charge determination



Physics  $O(\text{Hz}/\text{cm}^2)$

Beam background  $O(10\text{-}50 \text{ MHz}/\text{cm}^2)$

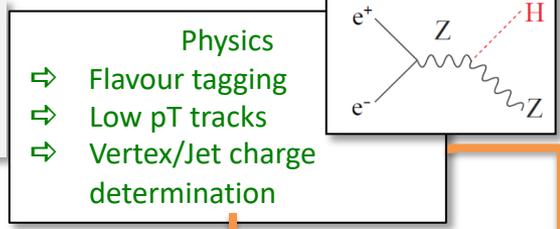
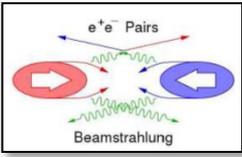
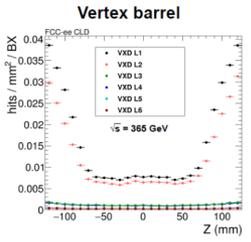


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- Physics
  - ⇒ Flavour tagging
  - ⇒ Low pT tracks
  - ⇒ Vertex/Jet charge determination

- Vertex reconstruction
  - ⇒ granularity
  - ⇒ Pitch  $\sim 17\text{-}20 \mu\text{m}$
  - ⇒  $(\sigma_{sp} \sim 3\text{-}4 \mu\text{m})$

- Material Budget
  - ⇒  $\sim 0.15\% X_0$  / layer
  - ⇒  $< 1\% X_0$  for the whole VTX
  - +  $\sim 0.3\% X_0$  for the beam pipe
  - +  $0.15\% X_0$  for  $5 \mu\text{m}$  Gold coating

Low material detectors & supports structures

$$\sigma_{d_0} = a \oplus \frac{b}{p \sin^{\frac{3}{2}} \theta}$$

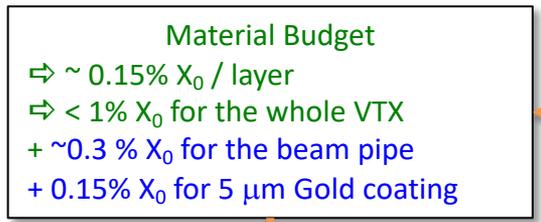
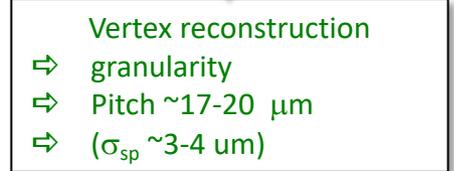
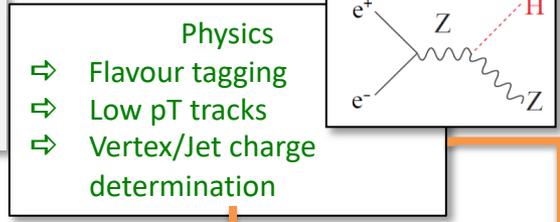
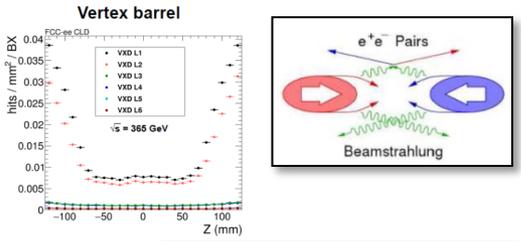
$a \simeq 5 \mu\text{m}$      $b \sim 15 \mu\text{m} \cdot \text{GeV}$  @ FCCee  
 $b \sim 10 \mu\text{m} \cdot \text{GeV}$  @ ILC

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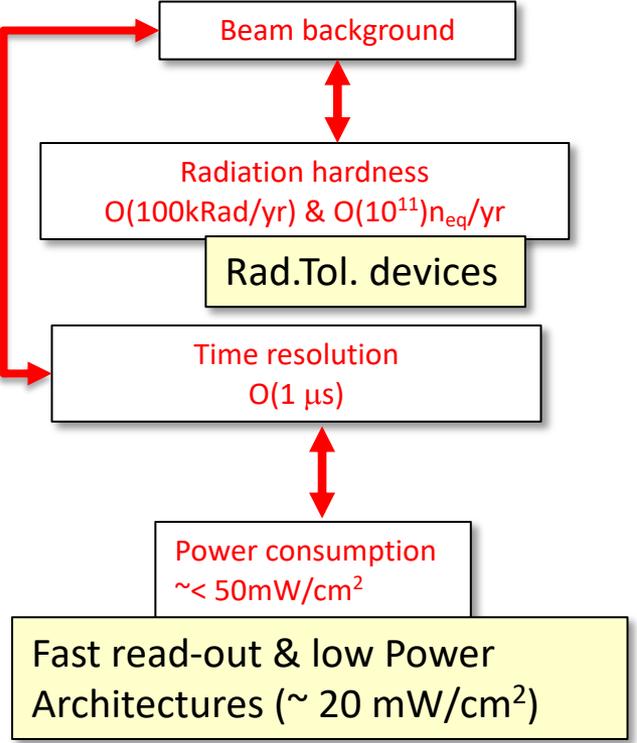
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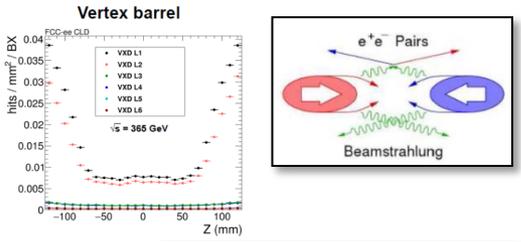
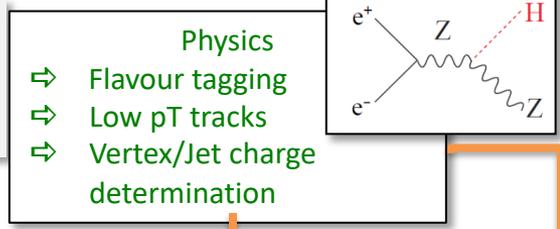
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Power pulsing (ILC) vs continuous beam (FCCee)

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# Higgs Factory Vertex detector requirements



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 Beam background  $O(10\text{-}50 \text{ MHz}/\text{cm}^2)$

Beam background

Radiation hardness  
 $O(100\text{kRad}/\text{yr})$  &  $O(10^{11})n_{\text{eq}}/\text{yr}$

Rad.Tol. devices

Time resolution  
 $O(1 \mu\text{s})$

Power consumption  
 $\sim 50\text{mW}/\text{cm}^2$

Fast read-out & low Power Architectures ( $\sim 20 \text{ mW}/\text{cm}^2$ )

Power pulsing (ILC) vs continuous beam (FCCee)

Cooling  
 Stiffness / Alignment

Vertex reconstruction  
 ⇒ granularity  
 ⇒ Pitch  $\sim 17\text{-}20 \mu\text{m}$   
 ⇒  $(\sigma_{\text{sp}} \sim 3\text{-}4 \mu\text{m})$

Material Budget  
 ⇒  $\sim 0.15\%$   $X_0$  / layer  
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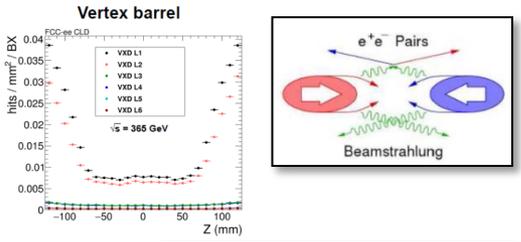
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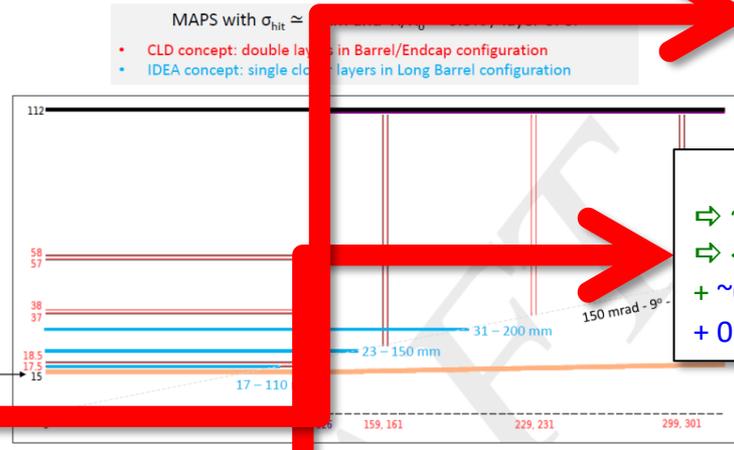
**Physics  $O(\text{Hz}/\text{cm}^2)$**   
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 CLD and IDEA Vertex Detectors designs (superimposed)

**Vertex reconstruction**

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(Figure: D. Contardo)

**Low material detectors & supports structures**

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**Beam background**

**Radiation hardness**  
 $O(100\text{kRad}/\text{yr})$  &  $O(10^{11}) n_{\text{eq}}/\text{yr}$

**Rad.Tol. devices**

**Time resolution**  
 $O(1 \mu\text{s})$

**Power consumption**  
 $\sim < 50\text{mW}/\text{cm}^2$

**Fast read-out & low Power Architectures** ( $\sim 20 \text{ mW}/\text{cm}^2$ )

**Cooling Stiffness / Alignment**

Power pulsing (ILC) vs continuous beam (FCCee)

5 single layers or 3 double layers ?  
 Inner (1.7 cm or lower ?) and outer radius are key factors

# Strategy: on the road to Higgs factories

Design, build and exploit CMOS pixels sensors  
with low material budget & high granularity

In order to contribute to the construction of a vertex & a tracking detector in a Higgs factory.

Approach the Higgs factories  
vertex detector requirements

MIMOSIS chip family (180 nm)



Maintain & develop the  
know how to build sensors  
to be installed in real  
experiments

Input for detector simulations

Optimize the parameters  
of the technology  
(e.g. sensitive layer)

Exploit fully the potential  
of the CMOS technology

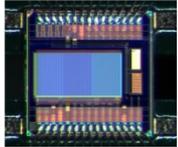
R&D 65 nm

Large surfaces  
(stitching)

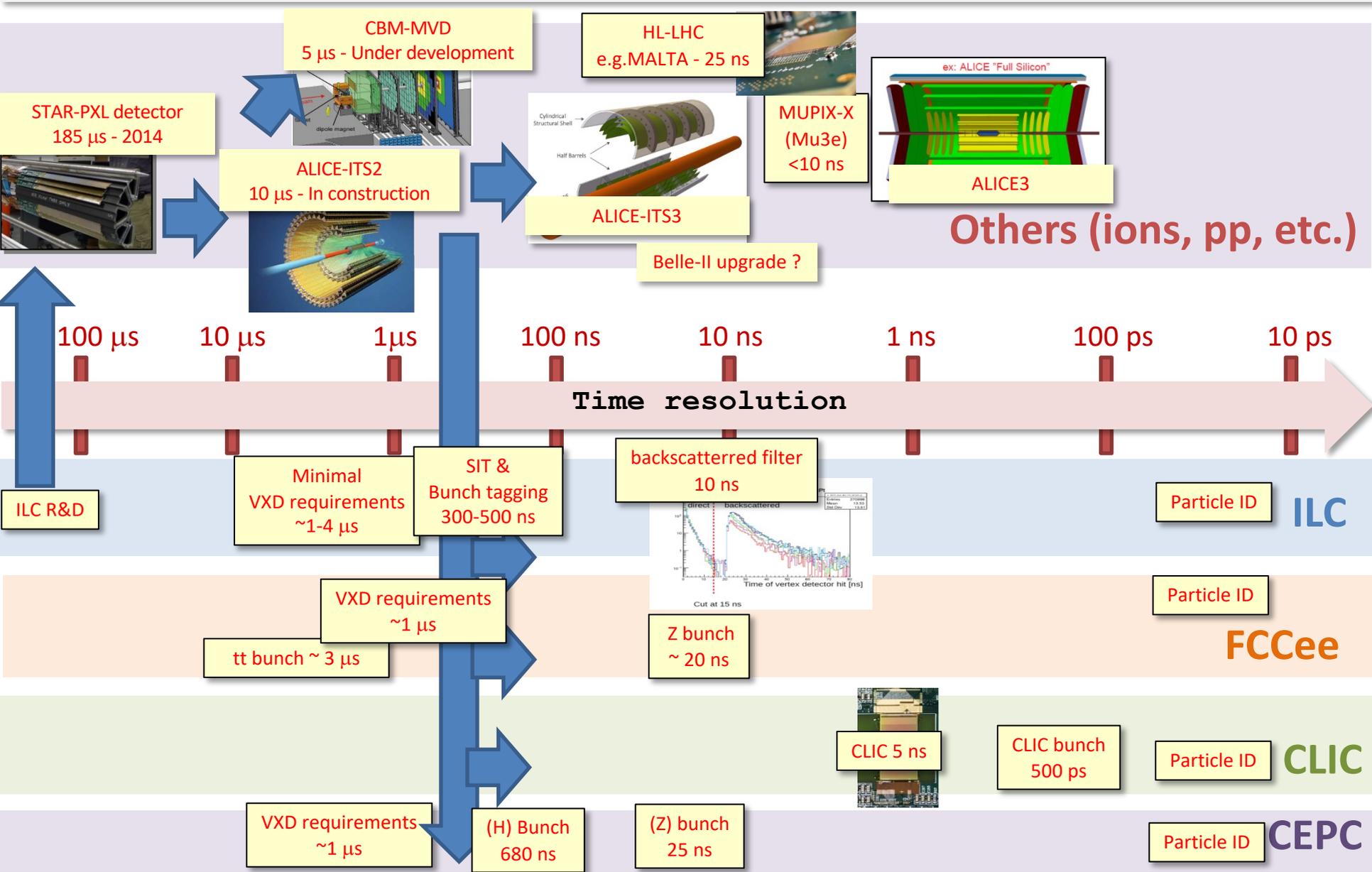
Bent sensors

Integration

Emerging technologies  
(e.g. double tier)



# Time resolution in the context of $e^+e^-$ colliders



# Synergies

K. Jakobs, FCC Physics Workshop, Feb 2022

ECFA recognizes the need for the experimental and theoretical communities involved in physics studies, experiment designs and detector technologies at future Higgs factories to gather. **ECFA supports a series of workshops** with the aim to **share challenges and expertise, to explore synergies in their efforts** and to respond coherently to this priority in the European Strategy for Particle Physics (ESPP).

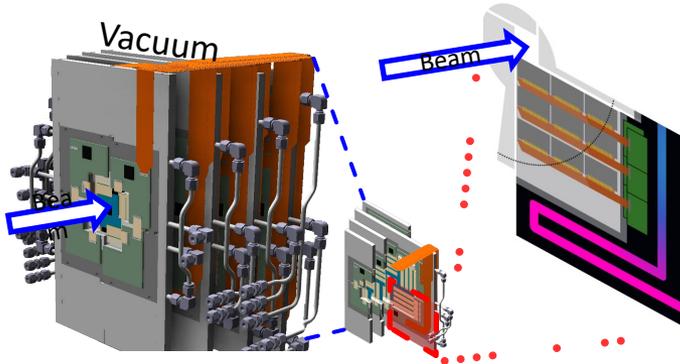
Goal: bring the entire  $e^+e^-$  Higgs factory effort together, foster cooperation across various projects; collaborative research programmes are to emerge



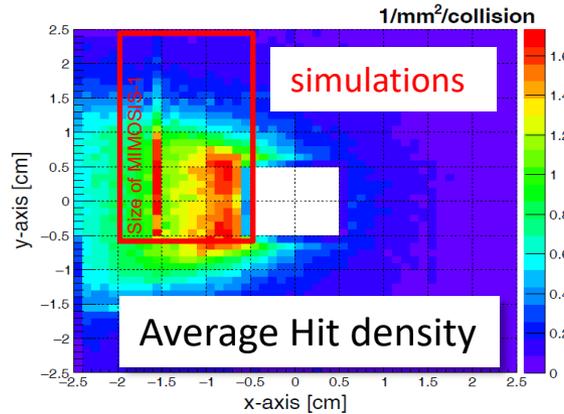
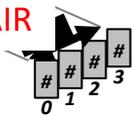
Important similarities between FCCee requirements & Heavy ions experiments (ALICE ITS3, ALICE3, EIC, etc.)

● Must happen or main physics goals cannot be met ● Important to meet several physics goals ● Desirable to enhance physics reach ● R&D needs being met

## Requirements



CBM-MVD@FAIR



Physics parameter	Requirements
Spatial resolution	~ 5 $\mu\text{m}$
Time resolution	~ 5 $\mu\text{s}$
Material budget	0.05% $X_0$
Power consumption	< 100 – 200 $\text{mW}/\text{cm}^2$
Operation temperature	- 40 $^\circ\text{C}$ to 30 $^\circ\text{C}$
Temp gradient on sensor	< 5K
Radiation tol* (non-ion)	~ $7 \times 10^{13} \text{ n}_{\text{eq}}/\text{cm}^2$
Radiation tol* (ionizing)	~ 5 MRad
Data flow (peak hit rate)	@ $7 \times 10^5 / (\text{mm}^2\text{s})$ > 2 Gbit/s

- 4 double-sided thin planar detector stations
- 100 kHz Au+Au @ 11 AGeV and 10GHz p+Au @ 30 AGeV
- Non uniform hit density in time and space
- High radiation environment, operating in vacuum

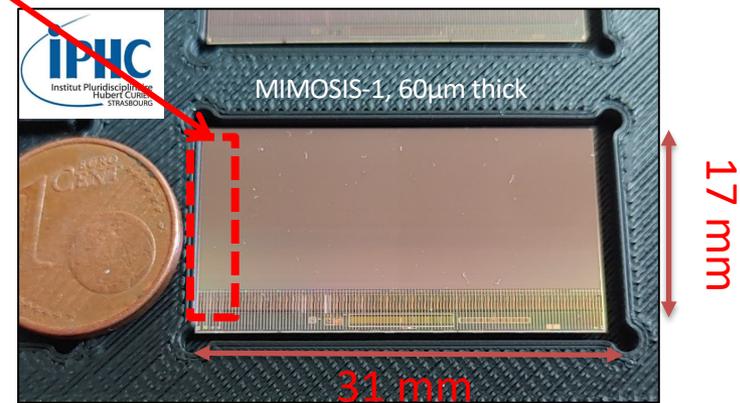
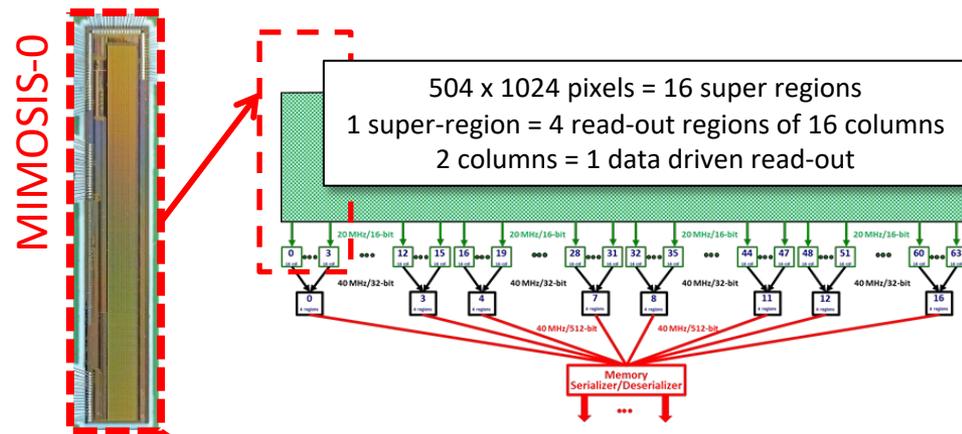
## MIMOSIS chip

- ✓ Based on ALPIDE architecture
- ✓ Discriminator on  $27 \times 30 \mu\text{m}^2$  pixel
- ✓ Multiple data concentration steps
- ✓ Elastic output buffer
- ✓ 8 x 320 Mbps links (switchable)
- ✓ Triple redundant electronics

Parameter	Value
Technology	TowerJazz 180 nm
Epi layer	~ 25 $\mu\text{m}$
Epi layer resistivity	> $1 \text{ k}\Omega\text{cm}$
Sensor thickness	60 $\mu\text{m}$
Pixel size	$26.88 \mu\text{m} \times 30.24 \mu\text{m}$
Matrix size	$1024 \times 504$ (516096 pix)
Matrix area	~ 4.2 $\text{cm}^2$
Matrix readout time	5 $\mu\text{s}$ (event driven)
Power consumption	40-70 $\text{mW}/\text{cm}^2$

# MIMOSIS roadmap

- 4 prototypes:
- MIMOSIS-0: = 2 regions
  - ✓ Tests (2018-2019)
    - Testability
- MIMOSIS-1: 1<sup>st</sup> full size prototype
  - ✓ Elastic buffer, SEE hardened
  - ✓ Fabricated in 2020
  - ✓ Lab/beam test campaign in 2021
- **MIMOSIS-2: Submitted last month (october 2022)**
  - ✓ On-chip clustering
  - ✓ Thicker epi layer tests
  - ✓ Test prototype for 1  $\mu$ s readout time
- MIMOSIS-3: final pre-production sensor
  - ✓  $\geq 2023$



⇒ architecture adaptable to a fast sensor for a FCC vertex detector  
⇒ Opportunity to study different designs/options

# MIMOSIS-1

## MIMOSIS tests

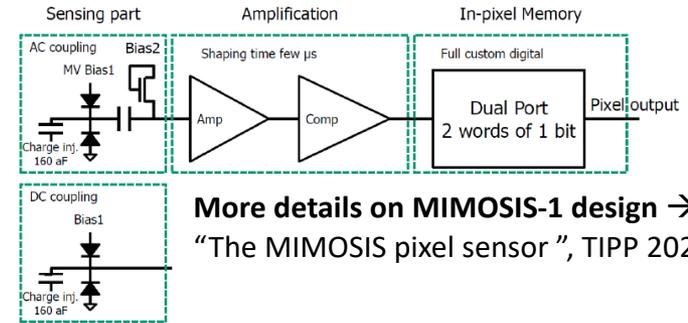
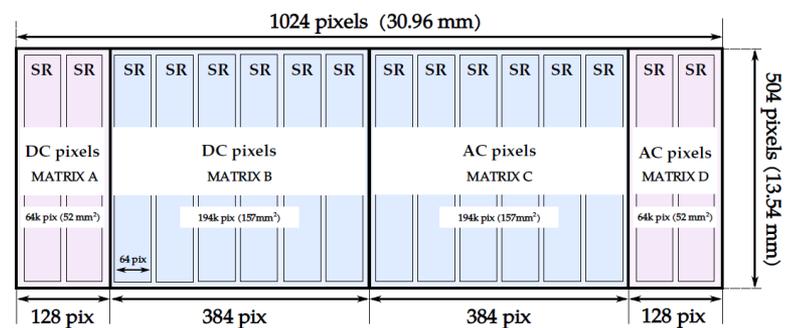
- ✓ Submatrices: DC/AC pixels
  - DC pixels: ALPIDE-derived
  - AC pixels: top bias up to > 20V
- ✓ 6 epitaxial variants (18 wafers)
  - Thinned down to 60 μm
  - Study Yield
  - Study charge collection / spatial res.
  - Explore performances after irradiation

## Intense test program in 2021:

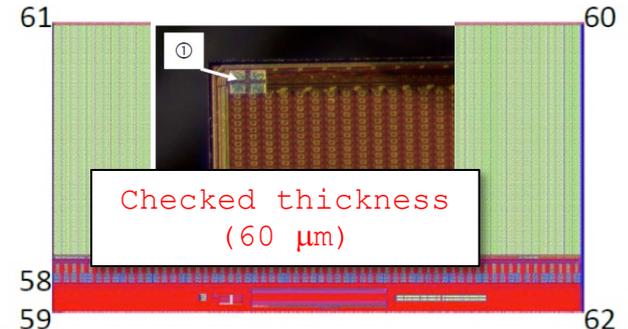
- ✓ Laboratory tests
- ✓ Irradiation tests

Ljubjana (TRIGA)	~1 MeV reactor neutrons
Karlsruhe (KIT)	~10 keV X-rays

- ✓ Beam tests @ DESY/CERN (3 campaigns)
- ✓ Latchup / SEE tests at GSI



More details on MIMOSIS-1 design → F. Morel, "The MIMOSIS pixel sensor", TIPP 2021

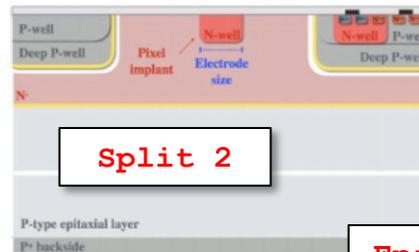


continuous n-layer

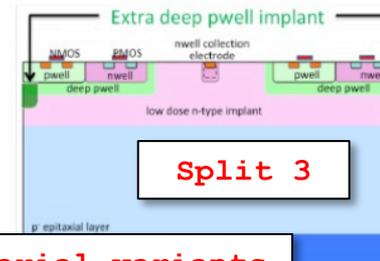
additional p-implant

gap in n-layer

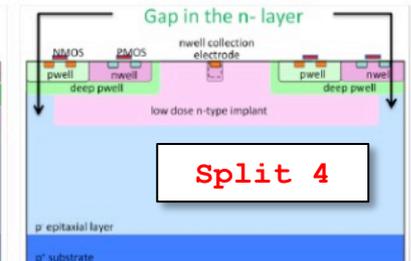
- standard process (3 available wafers)
- continuous n-layer (blanket) (3 wafers)
- additional p-implant (3 wafers)
- gap in n-layer (3 wafers)



Split 2



Split 3

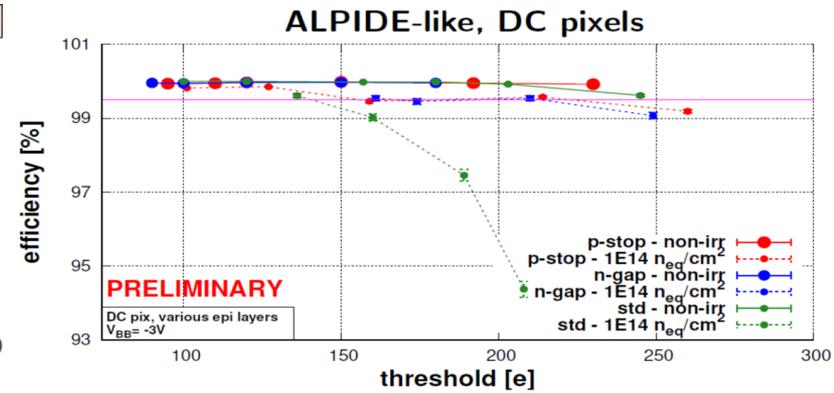
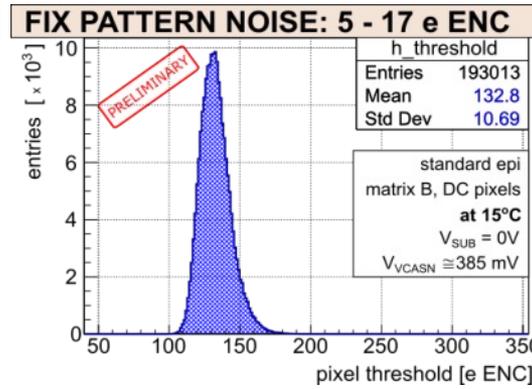
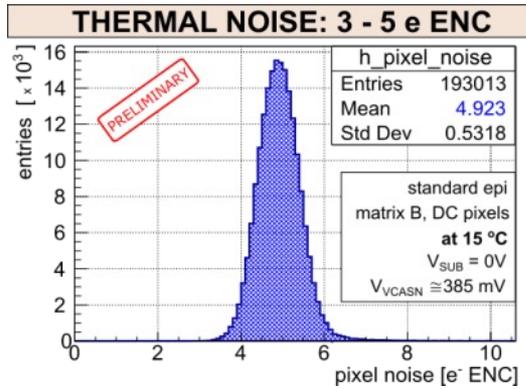


Split 4

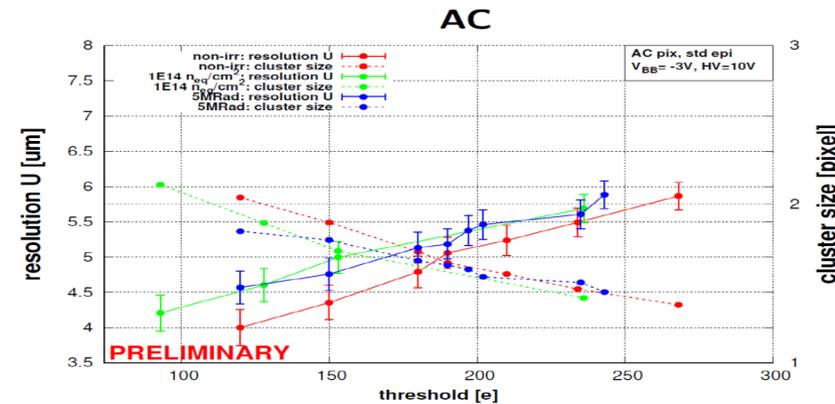
Epitaxial variants

Pic from: Munker, Vertex 2018, Status of silicon detector R&D at CLIC  
Carlos, TREDI 2019, Results of the Malta CMOS pixel detector prototype for the ATLAS Pixel ITK

# MIMOSIS beam test results



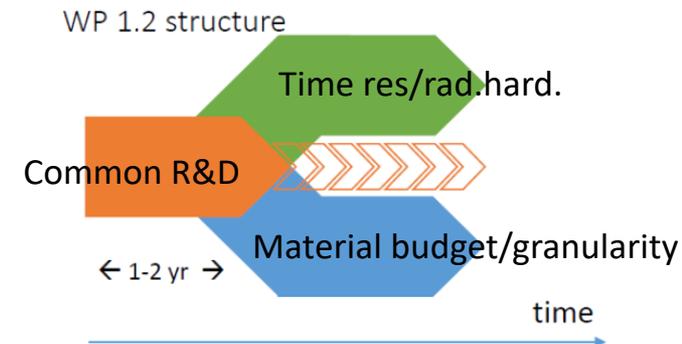
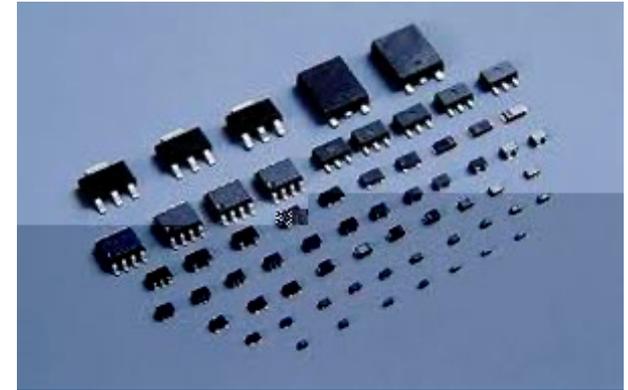
- Noise
  - ✓ DC pixels, (no back bias applied) @ room T°C
  - ✓ Pixel Noise ~ 3-5 e<sup>-</sup> ENC
  - ✓ FPN ~ 5-17 e<sup>-</sup> ENC
- Efficiency
  - ✓ ≥ 99.5 %
  - ✓ Time walk correction
- Cluster multiplicity
  - ✓ Typically in the 1-2 range
- Resolution as expected
- Fake rate probably very low
  - ✓ (< 10<sup>-6</sup>, tbc)



**MIMOSIS = a milestone for Higgs factories (5 μm / ≤5 μs)**

# From TowerJazz 180 nm (ALPIDE<sup>@ITS2</sup> & MIMOSIS) to TPSCo 65 nm (ITS3)

- 65 nm feature size technology
  - ✓ (ALPIDE & MIMOSIS fabricated in 180 nm)
  - ✓ Larger wafers (⇒ 30 cm)
  - ✓ More functionalities inside the pixel
  - ✓ Keeps pixel dimensions small ⇒ spatial res.
  - ✓ Potentially faster read-out
  - ✓ Lower Power consumption
- **TJ-65 nm available** (since June 2020)
  - ✓ Main driver: CERN EP R&D WP 1.2 & ALICE ITS-3 upgrades (involves other labs) ⇒ LS3 ~ 2024-26
  - ✓ Different requirements
    - EP: time resolution and radiation tol.
    - ALICE: granularity and material budget
    - Common R&D during the 1<sup>st</sup> years.



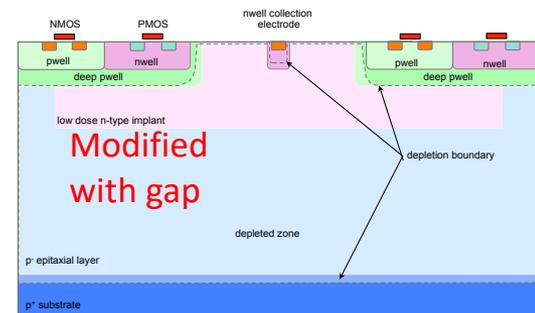
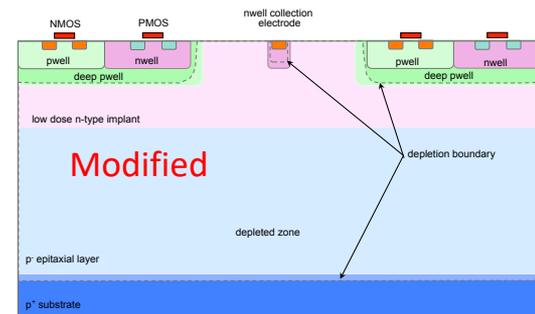
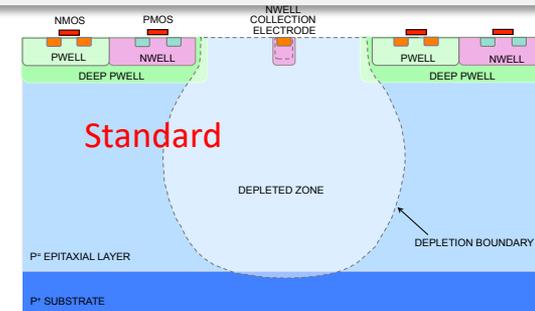
# The search for the optimal variant : depletion and doping

- ✓ 3 process variations for depletion control:
  - Standard (no modifications)
  - Modified (low dose n-type implant)
  - Modified with gap (low dose n-type implant with gaps)
- ✓ 4 process splits:
  1. **Default**
  2. First intermediate optimization
  3. Second intermediate optimization
  4. **Fully optimized process**
- ✓ Lower power consumption
- ✓ Possibly better radiation hardness

⇒ First submission: MLR1 (Q4 2020)

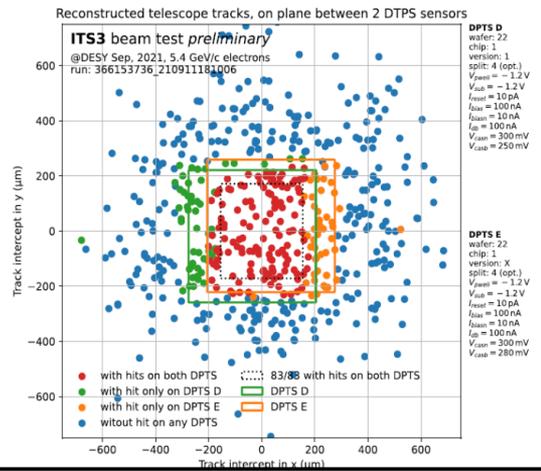
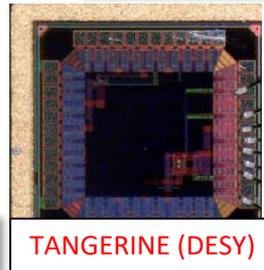
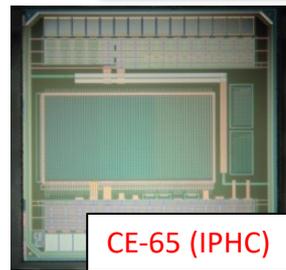
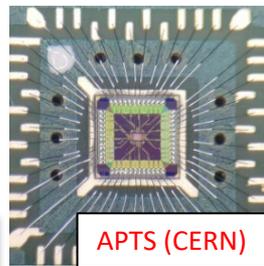
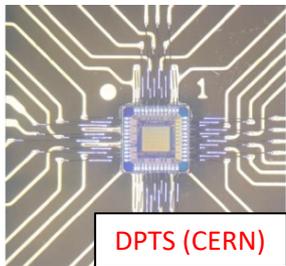
⇒ Synergy with Higgs factories requirements

⇒ Relation with foundries and access to options is a key factor

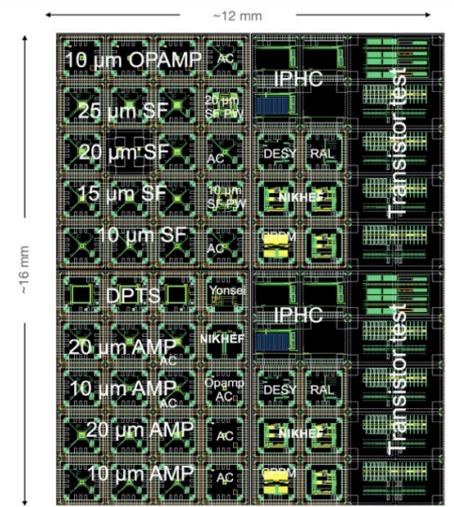


# 65nm MLR1

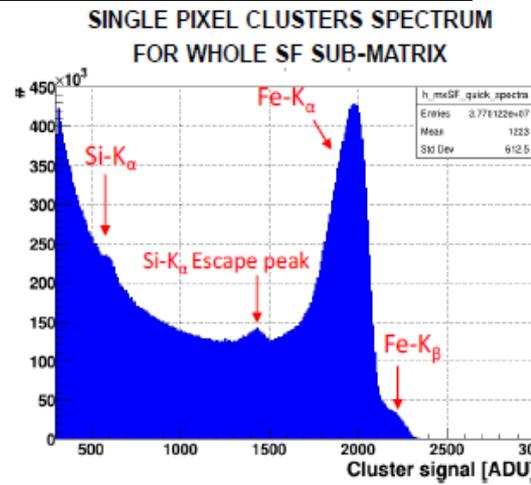
- Technology exploration
- Various pixel matrices and test structures
  - ✓ Radiation test structures
  - ✓ Amplification, DACs, LVDS, etc.
  - ✓ Pitch 15-25  $\mu\text{m}$
  - ✓ Epi variants



**DPTS in test beam**

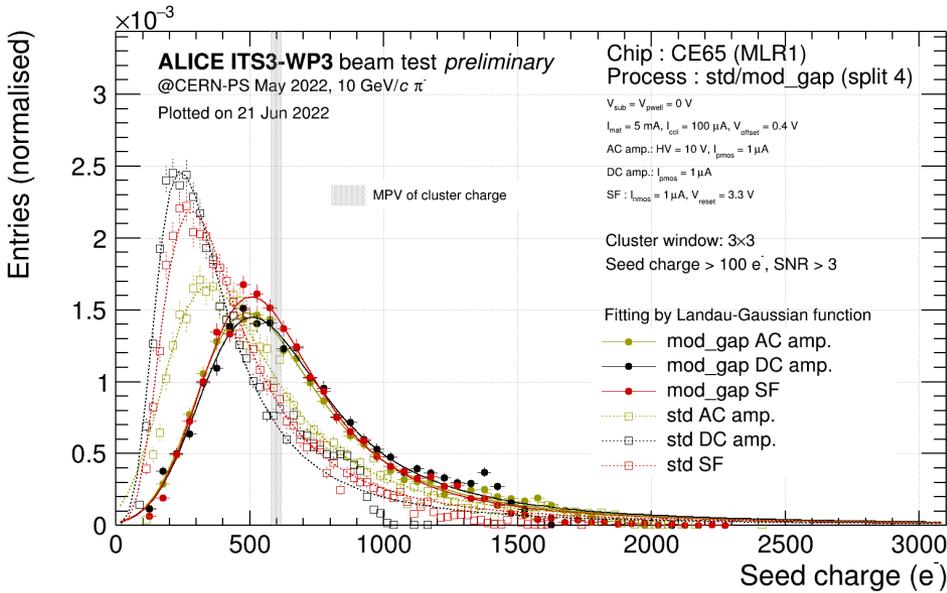
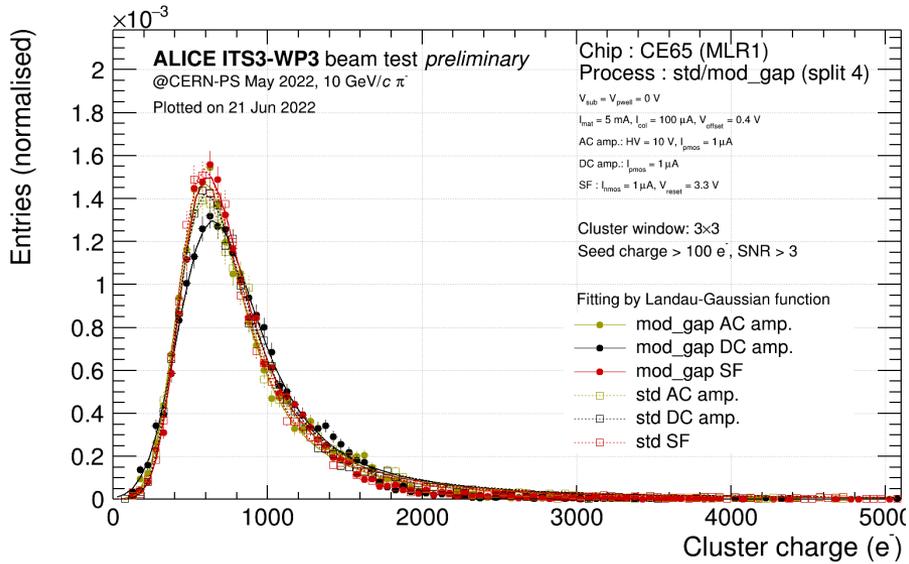


**IPHC, CERN, DESY, NIKHEF, Ral, Yonsei**



**CE\_65 with <sup>55</sup>Fe**

# CE65: Process modification reduces charge sharing

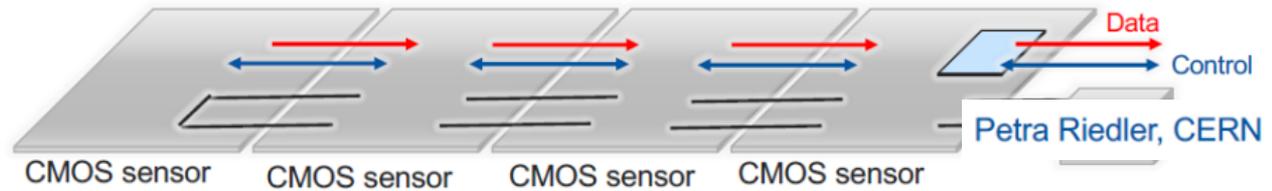


With modified process all the charge is mostly collected by a single pixel

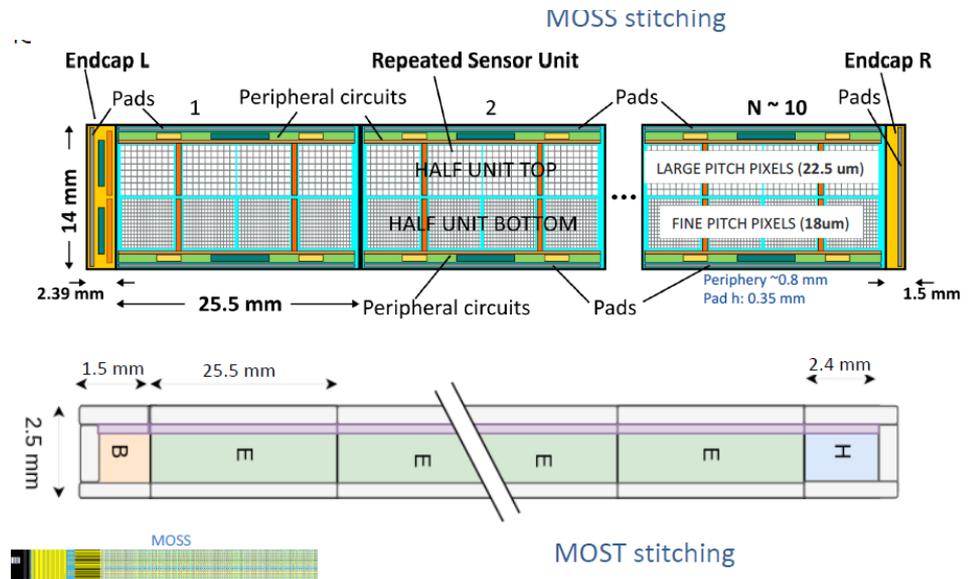
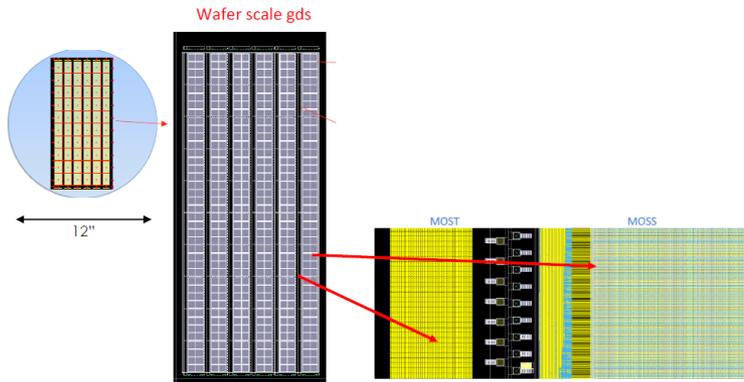
- ✓ Excellent charge collection efficiency
- ✓ Epi variants induce different charge sharing profile -> Resol Optimisation
- ✓ Epitaxial layer thickness estimates match expectations

# 65nm future plans

Overcoming the reticle size limitation  $\Rightarrow$  stitching



- Next submission: ER1 (2022)
  - CERN EP R&D WP 1.2 & ALICE ITS-3 upgrades (Submission: Q2 2022)
  - Monolithic Stitched Sensor (MOSS) driven by CERN
- ✓ Goal: study Stitching and interconnection (wafer scale)
  - Yield, Power distribution, signal routing, Noise, etc.

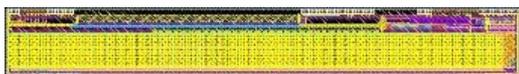


• Beyond ER1  $\Rightarrow$  ER2 (2022-23) dedicated to ITS-3

# Sensors with timing precision $< 1 \mu\text{s}$

## MIMOSIS-0fast prototype sensor

- Fabricated in mid-2022
- Derived from MIMOSIS architecture with faster front-end
- Explore timing in range 100-500 ns with power dissipation  $\ll 100 \text{ mW/cm}^2$
- 32x504 pixels ( $27 \times 30 \mu\text{m}^2$ )

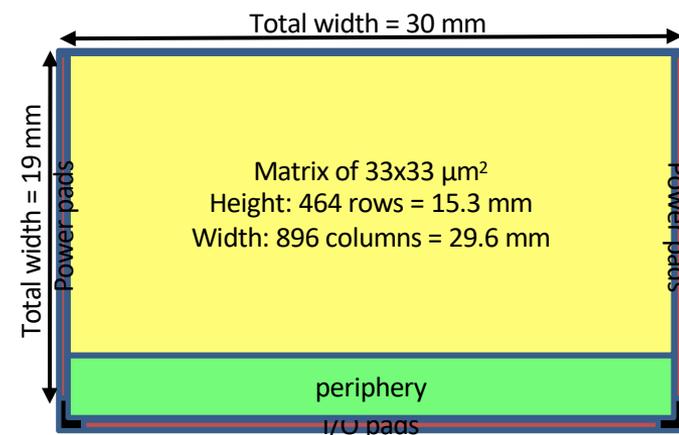


14.8 x 2.0 mm<sup>2</sup>

## OBELIX sensor Belle II upgraded VXD

- First version submission end of 2022
- Large collab: Bonn, CPPM, HEPHY, INFN, IPHC, Valencia
- Extension of TJ-MONOPIX-2 issued from R&D for ATLAS-ITK

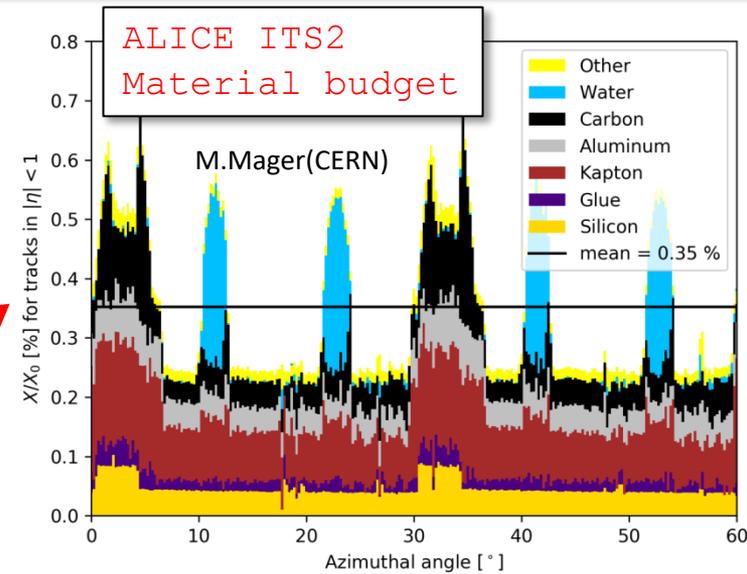
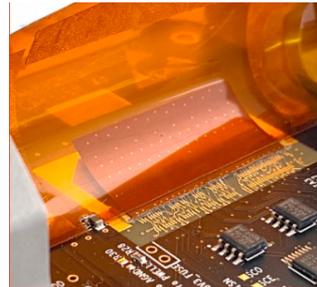
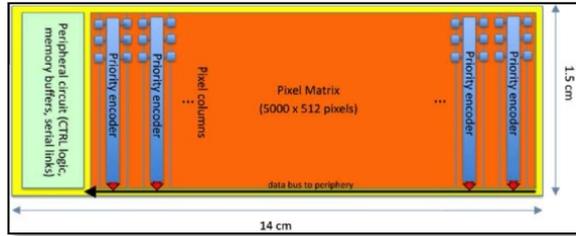
	OBELIX
Pitch	33 to 40 $\mu\text{m}$
Signal ToT	7 bits
Time stamp	7 bits
Integration time	25 To 100 ns
Bandwidth	$< 1 \text{ Gbps}$
Power	$< 200 \text{ mW/cm}^2$



# Material budget: Bent sensors & stitching

## Stitching:

- ✓ The way to go to minimize material budget



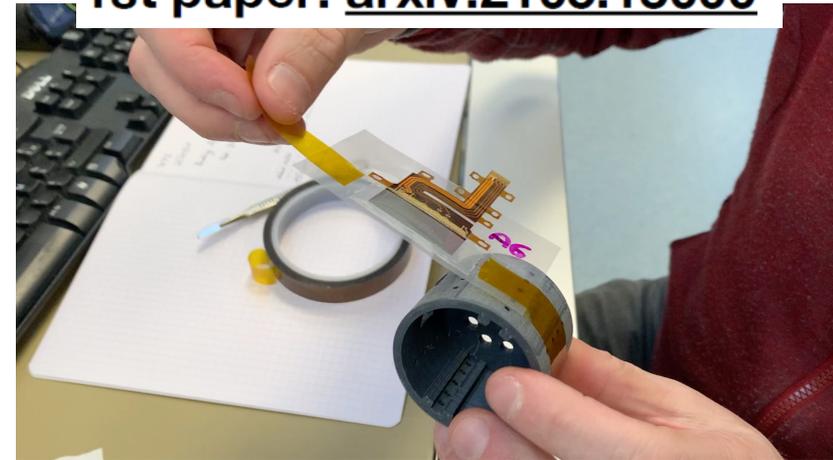
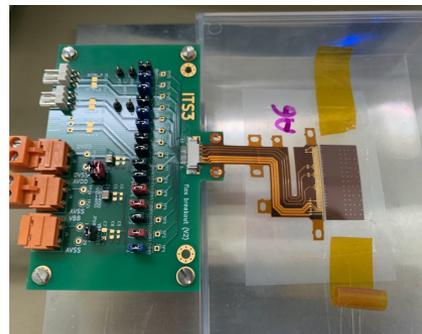
## ALICE-ITS3/CERN drive the R&D

- ✓ Cf. M. Mager Seminar: *ALICE ITS3 - a next generation vertex detector based on bent, wafer-scale CMOS sensors*

- <https://indico.cern.ch/event/1071914/>

## Micro-technics tests @IPHC

- ✓ collaboration with ALICE-ITS3
- ✓ Know-how acquired for bent bonding.



**1st paper: [arxiv:2105.13000](https://arxiv.org/abs/2105.13000)**

Bending / bonding  
Or Bonding / bending  
⇒ Functional tests

# Conclusion & Synergies in CMOS R&D

- Integration  $\Rightarrow$  not discussed here!
- CMOS Pixel Sensors are the baseline for Higgs factories
  - ✓ Requirements are within reach
- Strong dynamic of CMOS pixel Sensors R&D:
  - ✓ **180 nm : MIMOSIS series**
    - (5 $\mu$ m spatial res./  $\leq$ 5 $\mu$ s time res./ 60 $\mu$ m thickness / < 70 mW/cm<sup>2</sup>)
    - MIMOSIS-1  $\Rightarrow$  full size prototype being tested
    - MIMOSIS-2 to be submitted (Q3 2022)
  - ✓ **65 nm technology exploration**
    - First submission dec.2020 (MLR1)
    - **First test beam on CE\_65 chips @ CERN/DESY  $\rightarrow$  promising first results**
    - **2<sup>nd</sup> submission (ER1, Q1 2022): Stitching**
  - ✓ **Stitching** & large surfaces for very low mass detectors  $\Rightarrow$  Priority for Higgs factories in the future
    - Bent sensors test beam performed by ALICE
    - Material budget & Large pixelated surfaces
  - ✓ **Synergies** with
    - CERN R&D (ALICE ITS upgrades and EP R&D WP1.2)
    - R&D programs (e.g. AIDA-Innova, EURIZON, etc.)
    - Heavy ion experiments (e.g. ALICE beyond LS3/4 proposal, CBM, EIC)
    - Other experiments: Belle-II, etc.

Thanks for your attention